A New Fabrication Process of Ultrathick Microfluidic Microstructures Utilizing SU-8 Photoresist

Che-Hsin Lin¹, Gwo-Bin Lee², Bao-Wen Chang², Guan-Liang Chang¹

> ¹Institute of Biomedical Engineering ²Department of Engineering Science National Cheng Kung University

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Fabrication Techniques

Constant volume injection

- □ No edge-bead effect
- Good uniformity
- Good flatness
- Less photoresist wastage
- Higher SB and lower PEB temperature
 - □ Shorter processing time
 - Better structure definition
- A new mask design concept
 - □ Smaller exposed area
 - Discrete exposed area
- UV glue and SU-8 Bonding technique

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Fabrication processes



Constant volume injection of SU-8



Softbake at 120 °C and exposure



Post exposure bake at 65 °C



PGMEA developing



2nd flood exposure



Structure release and hardbake



UV glue bonding

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Ultrathick SU-8 structures



- Structure thickness: 1.5 mm
- Nearly vertical sidewall
- Good shape definition
- **Δ** Minimum feature width: 100 μm
- Aspect ratio > 15

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Thickness profile at the edge and photoresist uniformity



No edge bead

Reaching setting thickness within 3 mm



Substrate size: 10 x 10 cm²
Variation: ~ 3.1%

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UV glue bonding Technique



- Driven by capillary force
- Stopped by surface tension of UV glue
- Observation is not required
- High bonding strength can be obtained MML

MEMS design and Micro-fabrication Lab

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SU-8 micronozzles



Structure height: ~ 1 mm Width of nozzle: 250 μ m



Size: 1 cm X 1 cm Gas inlet via hole: 700 μm MML NCKU

A new pattern design concept

Micro channel: height 1 mm, width: 100 μ m



New design concept Conventional design

- Reduce exposed area.
- Separate exposed region.



Conventional design New design concept

- Channel collapsed with conventional design.
- Well-defined channel obtained with new design concept.

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Summaries

- A fast, low cost process was developed for fabrication of microfluidic devices.
- SU-8 PR layer thicker than1.5 mm could be formed by single coating.
- An easy, high strength bonding technique was used for sealing microchannels.
- A modified baking process was developed to get a better shape definition.
- A new mask design concept was proposed for fabrication of ultra-deep trenches.

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